

Abstract

**Lithographic Apparatus, Device Manufacturing Method, and
Device Manufactured Thereby.**

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A lithographic projection apparatus comprising: a radiation system for providing a projection beam of primary radiation; a support structure for supporting patterning means, the patterning means serving to pattern
10 the projection beam according to a desired pattern; a substrate table for holding a substrate; a projection system for projecting the patterned beam onto a target portion of the substrate; a radiation sensor which is moveable in a path traversed by the projection beam, for receiving primary radiation out of the projection beam, said sensor comprising: a radiation-
15 sensitive material which converts incident primary radiation into secondary radiation; sensing means capable of detecting said secondary radiation emerging from said material; and a filter material for preventing secondary radiation from traveling in a direction away from the sensing means.

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Fig. 1